

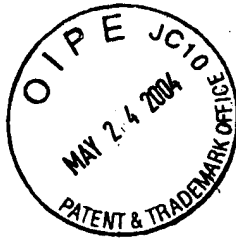
IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:
Eugene P. Marsh

Serial No.: 10/634,362

Filed: August 8, 2003

For: **ATOMIC LAYER DEPOSITION OF
METAL DURING THE FORMATION
OF A SEMICONDUCTOR DEVICE**



§
§
§
§
§
§
§
§
§
§

Group Art Unit: 2812

Examiner: Lynne Ann Gurley

Atty. Docket: 2003-0659.00/US

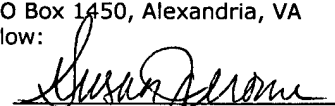
Confirmation No. 4954

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Certificate of Mailing (37 CFR §1.8)

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail, postage prepaid, in an envelope addressed to:
Commissioner for Patents, PO Box 1450, Alexandria, VA 22313-1450, on the date below:

May 20, 2004
Date


Signature

INFORMATION DISCLOSURE STATEMENT

In compliance with the duty of disclosure under 37 C.F.R. § 1.56, Applicant respectfully requests that this Information Disclosure Statement be entered and that the references listed on the attached Form PTO-1449 be considered by the Examiner and made of record. A copy of the listed reference is enclosed.

In accordance with 37 C.F.R. § 1.97(g), this Information Disclosure Statement is not to be construed as a representation that a search has been made or that no other possible material information as defined in 37 C.F.R. § 1.56(a) exists.

The following reference is submitted for the Examiner's review:

"Cobalt Metallorganic Chemical Vapor Deposition and Formation of Epitaxial CoSi_2 on Si(100) Substrate," Hwa Sung Rhee et al., Journal of the Electrochemical Society, 1999, pp. 2720-2724.

05/25/2004 HTECKLU1 00000068 133092 10634362

02 FC:1806 180.00 DA

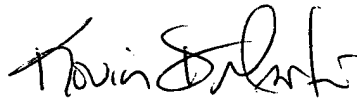
This Information Disclosure Statement is being submitted after the mailing of the first Office Action, but before the mailing of a Final Rejection or Notice of Allowance. The Commissioner is authorized to charge the fee set forth in 37 C.F.R § 1.17(p) of \$180 and any additional fees which may be required to Micron Technology Inc. Deposit Account No.13-3092, Order No. 2003-0659.00/US.

If there are any matters which may be resolved or clarified through telephone interview, the Examiner is respectfully requested to contact Applicant's undersigned agent at the number indicated.

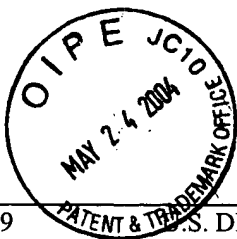
* * * *

Form PTO-1449 is enclosed herewith.

Respectfully submitted,



Kevin D. Martin
Reg. No. 37,882
Micron Technology, Inc.
8000 S. Federal Way
Boise, ID 83706-9632
(208) 368-4516
Agent for Applicant



Sheet: 1 of: 1

FORM: PTO-1449 (REV: 7-80)	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	Atty Docket No: 2003-0659.00/US	Serial No: 10/634,362
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (37 CFR 1.98(b)) (use several sheets if necessary)		Applicant: Eugene P. Marsh	
		Filing Date: August 8, 2003	Group: 2812

U.S. PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Name	Class	Subclass	
	AA					
	AB					
	AC					
	AD					
	AE					
	AF					
	AG					
	AH					
	AI					
	AJ					
	AK					
	AL					
	AM					
	AN					

FOREIGN PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Country	Class	Subclass	Translation	
	AO					Yes	No
	AP					<input type="checkbox"/>	<input type="checkbox"/>
	AQ					<input type="checkbox"/>	<input type="checkbox"/>

Initial	OTHER ART (including author, title, date, pertinent pages, etc.)		
	AR		"Cobalt Metallorganic Chemical Vapor Deposition and Formation of Epitaxial CoSi ₂ Layer on Si(100) Substrate", Hwa Sung Rhee et al, Journal of The Electrochemical Society, 1999, pp. 2720-2724
	AS		
	AT		

Examiner:	Date Considered:
-----------	------------------

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication with applicant.